

# SURFACE ASSEMBLY AND ULTRAFAST OPERATION OF ALL-NANOSCALE RESONANT-TUNNELING TRANSISTORS

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## Abstract

Realization of a robust nanotube-heterostructure tunneling transistors [*Solid State Comm.* **116**, 569 (2000)] requires the difficult formation [*Science* **293**, 76 (2001)] of a central nanoscale barrier separating a pair of outside metallic leads. Here I suggest an alternative surface-based assembly based on self-organization of one-dimensional metallic states on oxides and trapping well-resolved resonant orbitals in a central island. I present and explain the (universal) transistor characteristics and robustness. In addition, I calculate typical the island/level-to-gate capacitance to predict ultrafast (beyond-THz) switching but also document a limited importance of Coulomb blockade effects in the (nanotube) resonant-tunneling transistors.

**Keywords:** Ultrafast transistors, surface assembly, capacitance, Coulomb blockade, tunneling.

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## 1. Introduction

The all-nanoscale resonant-tunneling transistor [1] involves a pair of metallic leads separated by an ultra-small central barrier or island trapping resonant orbitals. The structure offers an automatic robustness toward defects, scattering, and room-temperature operation [1] and may be realized as a nanotube heterostructure [1, 2] or by repeated buckling a metallic nanotube [3]. Like the single-fullerene molecular transistor [4], the general design rests on tunneling [5] through well-resolved resonant levels trapped in the central barrier or molecular region of nanoscale extension. However, the specific design [1] also suggests electrostatic control through a close metallic nanotube gate [1] or scanning-tunneling microscope (STM) tip and hence offer a prospect of all-nanoscale, all-nanostructure circuit integration.

Surface-based assembly and growth [6] present a possible method to realize the necessary fabrication control for both all-nanoscale fabrication and ultimately circuit integration. In contrast, the traditional top-down fabrication techniques face significant challenges as we seek to decrease all feature sizes of the nanostructure devices. No easy approach exists for efficient integration or (mass) production as present top-down approaches involves a costly post-production functionalization. At the same time, the alternative molecular self-assembly mechanisms [4] offers limited possibilities for detailed control and complicates the gating and contacting. The quest for improving nanostructure operation motivates work on developing the necessary theory of (carbon) nanostructure transport, field-effect control, switching, dynamics [7] to minimize [1] the degree of fabrication control needed for successful device fabrication. The quest for device robustness and all-nanoscale device integration also motivates studies to (i) predict carbon-nanostructure interaction [8], that affects the nanostructure assembly, and (ii) bridge our understanding [6] from surface-based growth of semiconductor, metal, and oxide growth to the carbon-nanostructure formation processes.

In this paper I propose an alternative realization of the robust all-nanoscale resonant-tunneling

(RT) transistor while emphasizing the promise of surface-based growth in nanostructure fabrication. The proposed all-nanostructure RT device is based on the recently predicted [9] self-organization of atomic-scale one-dimensional electron gas (1DEG) on complex, flexible ionic surfaces. The proposed surface assembly also involves simple modifications to form a central island trapping resonant orbitals on the oxide surface and hence an ultra-compact all-nanoscale RT transistor. I establish the (universal) robust transistor characteristics and I calculate typical gate-to-resonant-level/island capacitance values to predict ultrafast switching operation and document a limited role of the Coulomb Blockade in the nanotube RT transistor realization.

## 2. Surface assembly of 1DEGs and resonant-tunneling transistors

Fig. 1 summarizes our recent prediction [9] of self-organization of one-dimensional metallic states on top of a complex, structurally flexible oxide, here on the  $(00\bar{1})$  surface of  $\kappa\text{-Al}_2\text{O}_3$ . The ultra-hard, metastable  $\kappa\text{-Al}_2\text{O}_3$  is normally produced in significant quantities for use in cutting tools but we predict that the atomic surface-relaxation processes make it a candidate for self-organized formation of atomic-scale metallic wires and one-dimensional electron gas (1DEG) systems. Specifically, the figure shows the high-electron-density iso-contour of the excess surface charge which is trapped in a (1DEG) system on top of single-Al zigzag chains on the  $(00\bar{1})$  oxide surface [9]. Besides the spatial variation of 1DEG the figure also indicates the corresponding fully relaxed ionic coordinates, both as obtained from detailed large scale ab initio density functional theory (DFT) calculations. Combining such DFT calculations with atomistic modeling of the dynamics we have further verified that the 1DEG surface state remains structurally stable over a wide range of temperatures ( $1\text{K} < T < 800\text{K}$ ) thanks to the intrinsic materials hardness of this cutting material [9, 6].

Fig. 2 illustrates how self-organized atomic-scale metallic wires [9] (top panel) upon modifications like in the previously investigated metallic-nanotube heterostructure systems [1, 3]

(bottom panel) provide realizations of both RT diodes and transistors. The formation [3] of nanoscale (double-junction) nanotube-heterostructures [1] provides the realization of RT and/or single-electron transistors. As illustrated in the top panel, a corresponding intentional damaging of the Al-zigzag-chain on the oxide surface causes junctions in the 1DEG and effectively the formation of a tunneling island. I stress how the oxide-surface location of the self-organized Al-zigzag-chain 1DEGs (Fig. 1) permits an easy access; in contrast to the previously investigated metallic-nanotube systems [1, 3], the new self-organized oxide 1DEGs should be relatively easy to post process into an all-nanoscale RT transistor realization, for example, by atomic manipulation by a STM tip.

### 3. Universal transistor robustness and characteristics

Figures 2 and 3 also provide a schematic illustration of the universal principle and intrinsically robust design of the all-nanoscale resonant-tunneling transistor. In short, such both of the transistors relies utilizes the RT transport mechanism but invokes traditional field-effect control to enable this tunneling current by adjusting the energy position of the well-resolved resonant-energy level [1]. I stress how this description and the full analysis (based on a combined DFT and nonequilibrium Green function study [5]) summarized in previous studies [1] is universal and hence is also directly applicable to the presently proposed Al-zigzag-chain RT transistor realization, Fig. 2. I also emphasize how comparing the pair of lower-panel inserts of Fig. 2 (showing the spatial variation of the resonant-orbital wavefunction in the absence and presence a local defect) exemplify the automatic robustness: a controlled RT transistor effect will arise in either case (since the nanoscale extension guarantee a well-resolved set of resonant-energy levels [1]). The presence of defect will adjust the specific values of the resonant-level tunneling rates  $\Gamma_{L/R}$  but the transistor characteristics, Fig. 3, is still universal as it is completely scaled in terms of  $\Gamma_{L/R}$ , Ref. [1]. Fig. 3 also show that the general all-nanoscale RT transistor operation is equally robust toward inelastic scattering or room-temperature operation. Finally, I stress that

a finite Coulomb blockade effect causes no more than a simple adjustment of the resonant-level gate control  $E_{\text{orb}}(\Phi_{\text{gate}})$ .

#### 4. Gate control, Capacitance, Coulomb blockade, and switching

To provide a crude description of the gate-control, Coulomb-blockade effects, and of the all-nanoscale RT transistor switching times, I analyze the contribution to the total resonant-level capacitance  $C_{\text{tot}}$  and associated Coulomb-blockade charging energy

$$\delta E_{\text{CB}} \equiv \frac{e^2}{2C_{\text{tot}}}. \quad (1)$$

Specifically, I separate this total resonant-orbital capacitance

$$C_{\text{tot}} = C_{\text{gate}} + C_{\text{orb}} + C_{\text{leads}} + C_{\text{env}} \quad (2)$$

into contributions describing the external gate control, the resonant-orbital self interaction [10], the orbital-to-metallic-leads coupling, and the possible interaction with the remaining environment, respectively. This separation of the resonant-orbital capacitance permits two important conclusions:

A. The traditional Coulomb blockade effect *decreases* in value and importance as we shorten the extension  $l$  of the central island and approach the all-nanoscale RT transistor design [1] (even though the effective value of the self-interaction capacitance  $C_{\text{orb}}$ , of course, increases dramatically [10]), as also discussed in Ref. [3].

B. The all-nanotube RT transistor supports ultrafast (beyond-THz) switching and external-gate-control operation. The ultrafast operation is limited not by the capacitive coupling but by the significant values of the resonant-level tunneling,  $\Gamma_{\text{L/R}} > 10$  THz, which determines the switching rate, Fig. 3.

Conclusion A applies since — in both of the proposed RT transistor designs as a nanotube heterostructure [1, 3] or as an double-interrupted Al-chain structure, Fig. 2 — we are starting with

a nanoscale-metallic wire of a given nano- or subnano-meter cross section, labor to nanosize the value of island length  $l$ , and consequently enhance the value of the resonance-to-lead coupling  $C_{\text{leads}} \propto 1/l$ . Traditional Coulomb blockade effects thus decreases  $\delta E_{\text{CB}}(l) < (e^2)/(2C_{\text{leads}}) \propto l$ , whereas the level separation  $\delta E_{\text{orb}} \propto 1/l$  enhances to make the RT transport effects dominant. From the characterization of the nanotube-heterostructure RT transistor [3] it follows that the cross over,  $\delta E_{\text{orb}}(l) > \delta E_{\text{CB}}(l)$  should occur for nanotubes already around  $l \sim 30\text{nm}$  (whereas the cross-over will be significantly smaller for the here-proposed design as a double-interrupted Al-chain structure, Fig. 2).

The argument for conclusion B comprises two parts, namely that both the external gate control and the RT transport mechanism tolerate ultrafast (beyond-THz) switching and operation. The possibility for ultrafast gate operation follows directly from a previous theory study [1] of the external electrostatic control in the nanotube-heterostructure RT transistors. A finite-element analysis using a DFT-based approximation for the nanotube-heterostructure electrodynamics response [1, 8] shows how the application of a finite gate voltage  $\Phi_{\text{gate}} \approx 3V$  adjusts the island potential sufficiently to enable charge transfer (tunneling) across the resonant orbital. A rough estimate (ignoring the Coulomb blockade effect) for the gate capacitance is thus given by  $C_{\text{gate}} > \sim e/\Phi_{\text{gate}} \sim 0.1 \text{ aF}$ . Assuming a typical contact resistance  $R_0 \approx 10 \text{ k}\Omega$  for the nanotube gate, this value provides us with an estimated cut-off frequency  $1/R_0 C_{\text{gate}} \gg 1 \text{ THz}$ .

To complete the argument for conclusion B, I stress that the universal operating characteristic, Fig. 3, and the associated automatic robustness is separately demonstrated [5] to tolerate beyond-THz operation under some general conditions [5]. Starting from a full non-equilibrium Green function calculation of the time-dependent RT electron kinetics it is possible to show that the qualitative nature of the transistor-transport current (shown in Fig. 3 and presented in Ref. [1]) remains invariant as long as the frequency does not exceed the thickness of the Fermi sea in the (metallic!) leads. There will certainly be no restraints on the validity/robustness of

the RT transport description from this condition in the THz regime. Instead, it follows that the ultrafast operation is limited only by the switching rate set by the resonant-orbital transit times, that is, by the significant values of the resonant-level tunneling,  $\hbar\omega_{\max} \sim \Gamma_{L/R} \sim 10$  THz.

## 5. Conclusions and acknowledgments

In this paper I have proposed a new realization of the robust all-nanoscale resonant-tunneling transistor based on surface assembly mechanisms. I have furthermore summarized the universal transistor characteristics and estimated the capacitive coupling, the magnitude of the Coulomb blockade effects and documented the feasibility of ultrafast, beyond-THz, transistor switching and operation.

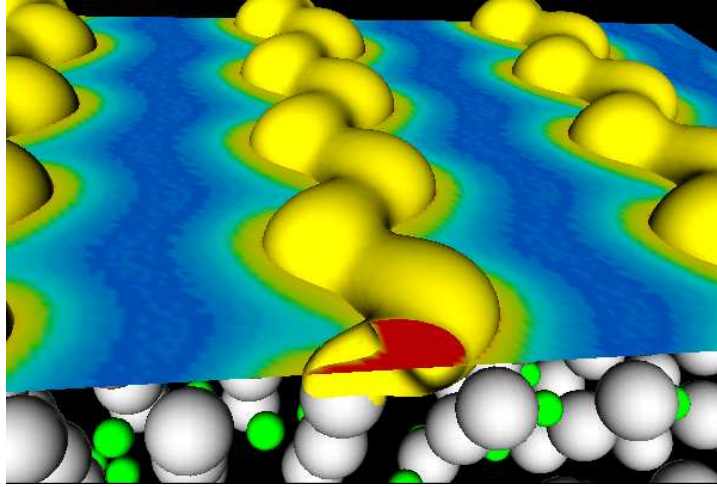
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- [10] DFT calculations for *isolated* nanoscale molecules/nanostuctures can provide estimates for  $C_{\text{orb}}$  (typically several eVs); However, the concept  $C_{\text{orb}}$  obviously have very limited applicability for such all-nanoscale structures.

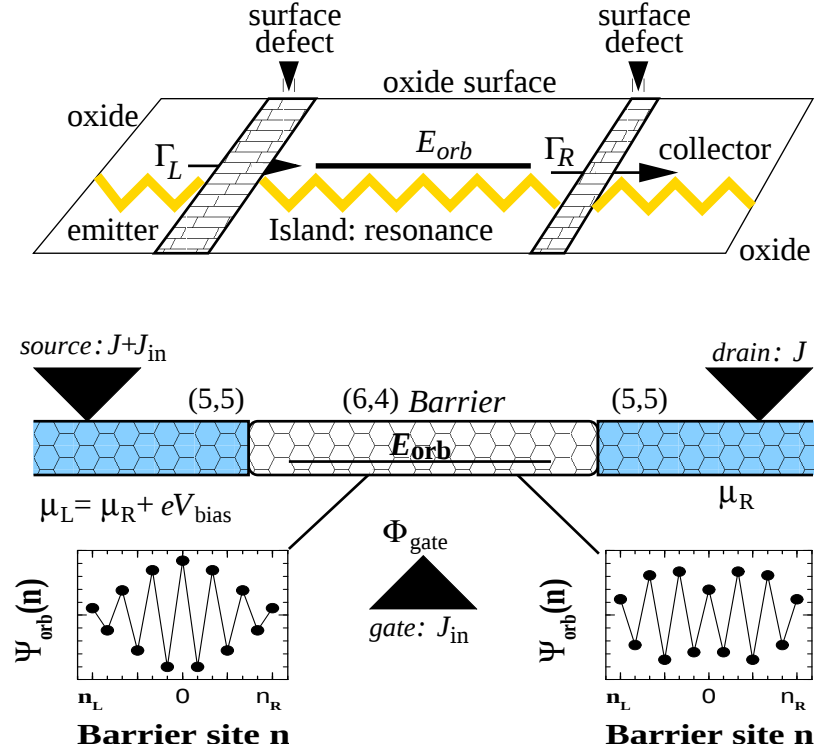
## FIGURES AND CAPTIONS



**Figure 1:** Self-organized formation of atom-scale conducting wires predicted [9] on complex, structurally-flexible oxide surfaces. The figure shows the high-electron-density isosurface of the one-dimensional metallic electron gas (1DEG) systems predicted to self-organize on the  $(00\bar{1})$  surface of  $\kappa\text{-Al}_2\text{O}_3$ . Forming an Al-terminated surface of the ultra-hard  $\kappa\text{-Al}_2\text{O}_3$  oxide (used extensively in cutting-tool applications) introduces very strong electrostatic forces which in turn cause a dramatic reorganization of the outermost Al atoms [9]. For the  $(00\bar{1})$  surface, however, this relaxation is frustrated as excess surface charge is pushed to the oxide surface to ensure charge neutrality [9]. Instead the complex

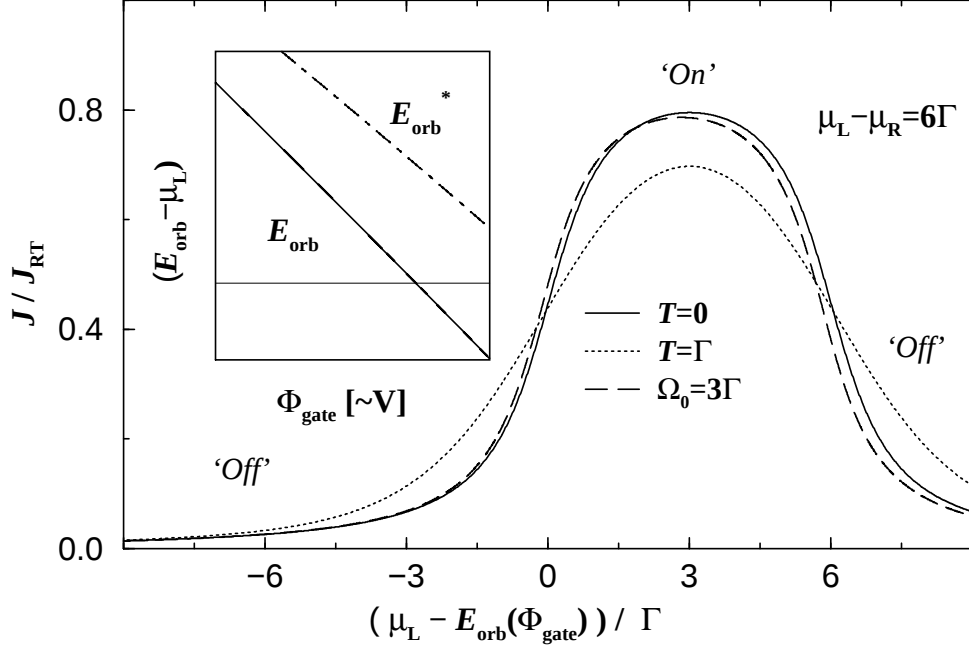


oxide traps a metallic surface state (shown) on top of the outermost zigzag single-Al-atomic chains. This self-organization mechanism produce atom-scale 1DEGs which is structurally stable across a large temperature interval ( $1\text{K} < T < 800\text{K}$ ) [9]. The self-organized 1DEGs may function both directly as atom-scale metal wires and leads of high electric conductivity [9] and even, with further modification, Fig. 2, provide a starting point for fabrication of all-nanoscale robust resonant-tunneling transistors [1, 3].



**Figure 2:** Sample realizations and automatic robustness of all-nanoscale resonant-tunneling diodes and transistor devices by functionalization of surface-oxide 1DEGs [9] (top panel) and metallic nanotubes (bottom panel) [1, 3]. In both realizations, a nanoscale  $L_B$  section or island separates a pair of outside Al-wire or metallic nanotube leads to suppress the linear-response transport. The nanoscale island/barrier traps a set of well-resolved resonance energies  $E_{orb}$  [1] and applying a finite applied bias  $\mu_L - \mu_R$  can enable a tunneling current through the associated resonance orbital  $\Psi_{orb}$ . The lower panel illustrates, how, in both realizations, the presence of a close metallic gate [1] at potential  $\Phi_{gate}$

even provides resonant-tunneling transistor operation by adjusting the resonant-level energy position  $E_{\text{orb}}(\Phi_{\text{gate}})$ . Finally, *the pair of insets* illustrate how the resonant-tunneling design ensures robustness, *i.e.*, an automatic insensitivity toward scattering by local defects (and inelastic interactions); see text.



**Figure 3:** Universal and robust nanostructure transistor operation specified by the value of the tunneling rate,  $\Gamma = \Gamma_L + \Gamma_R$ , and by the peak current,  $J_{\text{RT}} = 4\Gamma_L\Gamma_R/\Gamma$ , of the all-nanoscale resonant-tunneling device, Fig. 2. The figure assumes an implicit control  $E_{\text{orb}}(\Phi_{\text{gate}})$  of the resonant-orbital energy position  $E_{\text{orb}}$  by the potential of the close metallic-nanotube gate (Fig. 2). The figure compares the predicted gate-variation in the transistor current assuming (i) zero-temperature and no scattering (solid curve), (ii) a strong generic inelastic scattering [1] (dashed curve), and (iii) room-temperature operation (dotted curve). Note that Coulomb blockade effects can cause no more than a simple (and for the nanotube realizations negligible) adjustment of the implicit gate control  $E_{\text{orb}}(\Phi_{\text{gate}})$ .